

ELECTRON BEAM MICROANALYSER

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Inventor(s): NOJI TAKETOSHI
Applicant(s): SHIMADZU CORP
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Abstract

PROBLEM TO BE SOLVED: To calculate the elemental distribution of a sample in an electron beam microanalyser.

SOLUTION: An electron beam microanalyser performing the elemental analysis of the surface of a sample S by X-rays emitted from the sample S irradiated with electron beam 71 is equipped with an electron beam scanning part 2 performing the fast secondary scanning on the sample by the electron beam 71, an X-ray spectroscopy scanning part 3 performing the scanning of the spectral wavelength of an X-ray spectroscopy 4 and a control part 5 controlling both of the electron beam scanning part 2 and the X-ray spectroscopy scanning part 3 at the same time. By the simultaneous control of the electron beam scanning part 2 and the X-ray spectroscopy scanning part 3 by the control part 5, a secondary X-ray signal at a scanned spectral wavelength is calculated to obtain a secondary X-ray scanning image of a predetermined wavelength.

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